



# Electromigration-Aware Reliability Optimization of MCPM Layouts Using PowerSynth

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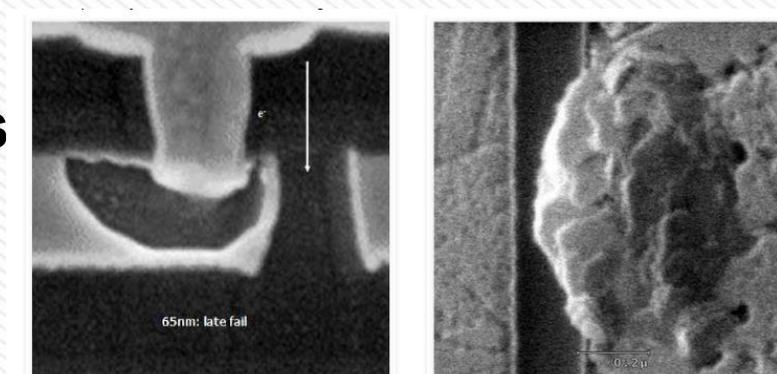
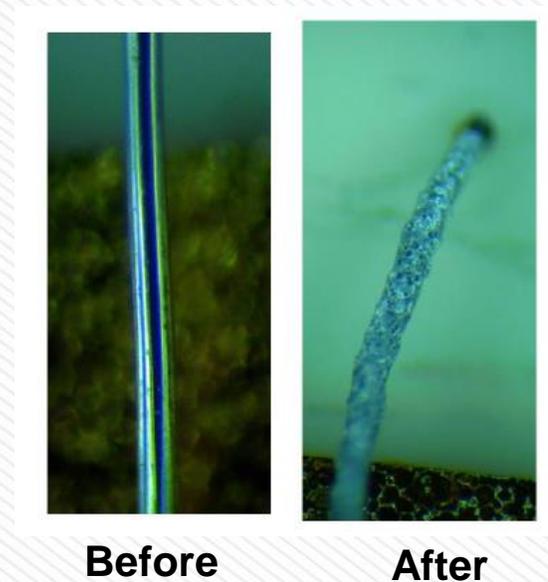
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## □ What is Electromigration (EM) ?

- A material migration based on the flow of current through it
- A diffusion-controlled process.
- Accelerated by:
  - High current density
  - High temperature

## □ Why EM is a concern in Power Modules ?

- Recent trend toward high power density
  - Increasing current density and temperature
- Reliability of the interconnects: Wire bonds, solder bumps
  - Void formation: Open circuit
  - Hillock formation: Short circuit



void formation      Short ckt formation

EM impact on interconnects



# EM Risk Assessment Modeling Approaches



## □ Analytical & Experimental

- combined effect of high current and high temperature on Ag, Cu, and Au wire bonds [1]
- An electrical-thermal-mechanical coupled EM analysis in a bonding wire of a power module [2]
- Current density variation impact on wire bond resistance and die attach solder [3]
- Optimizing solder bump structure through solder bump parametric variation in [4]
  - Solder material
  - Solder bump diameter/pitch
  - Geometry
- Solder bump distribution orientation variation for optimization [5]

**All efforts are based on manual parameterization and experimental studies**

[1] P. Lall et. al., "Study of Electromigration in Cu and Ag Wirebonds Operating at High Current in Extreme Environments," in IEEE iTherm, 2017

[2] M. Kato et al., "Electromigration Analysis of Power Modules by Electrical-Thermal-Mechanical Coupled Model," in ASME IMECE, Nov. 2019.

[3] H. Luo et al., "Study of Current Density Influence on Bond Wire Degradation Rate in SiC MOSFET Modules," IEEE JESTPE, 2020.

[4] M. Montazeri et al., "Vertically Stacked, Flip-Chip Wide Bandgap MOSFET Co-Optimized for Reliability and Switching Performance," IEEE JESTPE, 2021.

[5] C. Hau-Riege and Y. Yau, "Electromigration Reliability of Solder Balls," in IEEE IPFA, 2018

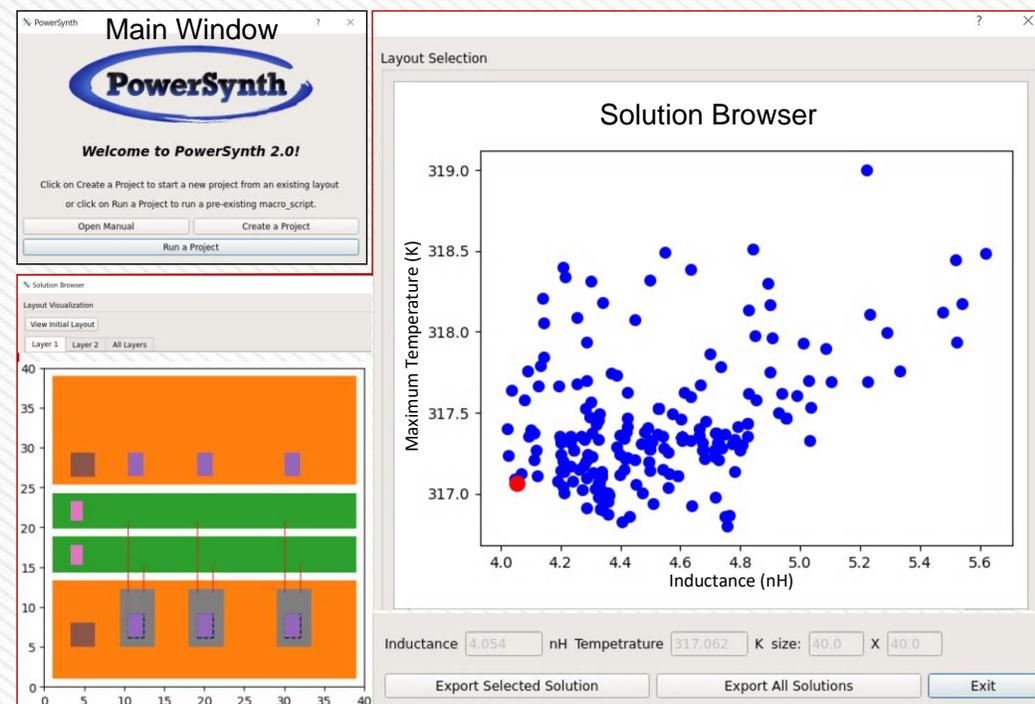
## □ Motivations

- No design automation effort for EM assessment
- High density power module optimization requires EM-aware reliability optimization
- Need EDA tools for EM-aware layout optimization
- **Our solution: EM-Aware PowerSynth 2 [1]**

## □ Contributions

- Current density distribution for DC and AC
- A generic EM-aware risk assessment workflow
  - Analytical
  - Data-Driven

- Case studies demonstration: Power module with solder bumps and wire bonds
- EM-aware electro-thermal optimization using PowerSynth 2



PowerSynth 2 GUI

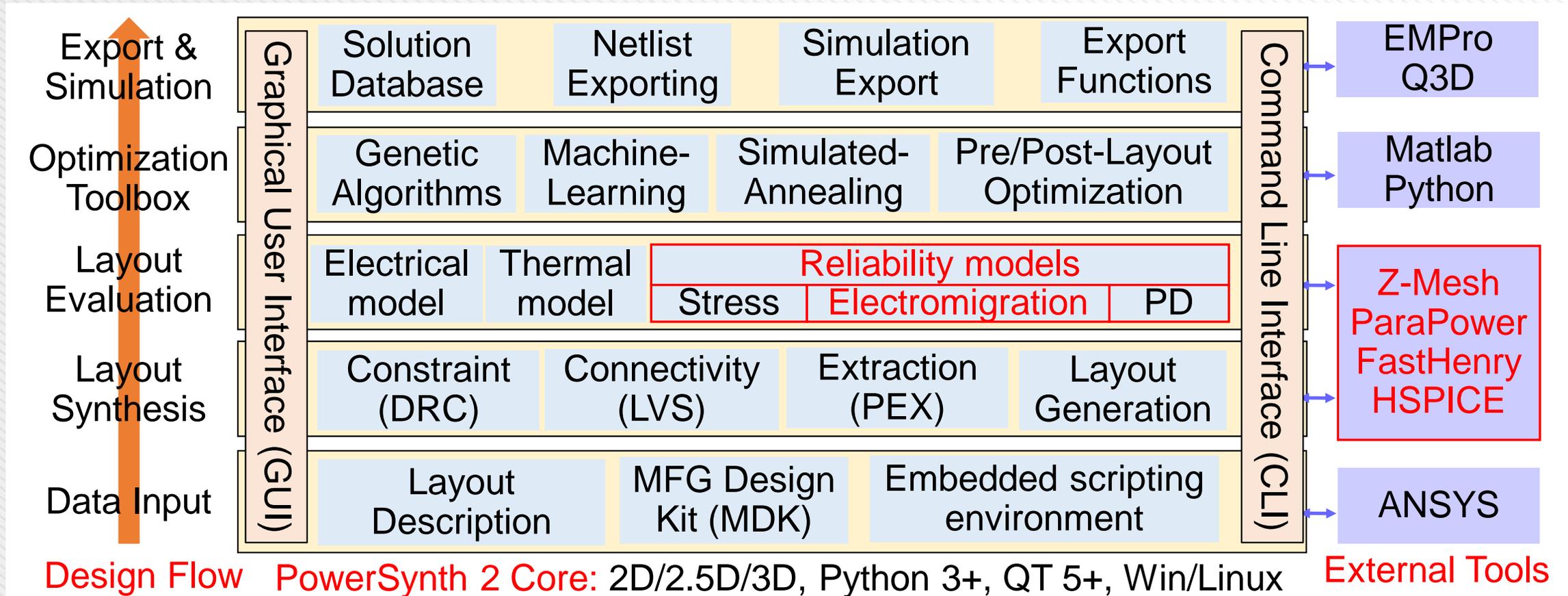
[1] I. Al Razi et. al., "Hierarchical Layout Synthesis and Optimization Framework for High-Density Power Module Design Automation," ICCAD, 2021.



# PowerSynth 2



## Architecture



[1] PowerSynth Release Website: <https://e3da.csce.uark.edu/release/PowerSynth/>



# Reliability Optimization Using PowerSynth



## ❑ PowerSynth 2 allows:

- Integration external modeling efforts/tools through APIs
  - ParaPower: Army Research Lab (ARL) developed thermal and stress evaluation tool
- Handling both types of interconnects (i.e., wire bonds and solder joints)
- Considering arbitrary layer stack
- Material library modification

## ❑ To perform reliability optimization, it requires efficient, and accurate models

## ❑ Currently, MCPM layouts can be optimized for two major reliability threats:

- Thermal cycling impact minimization [1]
  - Transient thermal model for 2D MCPM layouts
  - Phase change material (PCM) consideration
- Electromigration associated risk assessment
  - Current density modeling through Z-Mesh tool

[1] Imam Al Razi, David Huitink, and Yarui Peng, "PowerSynth-Guided Reliability Optimization of Multi-Chip Power Module", APEC, 2021.

[2] ARL ParaPower, "<https://github.com/USArmyResearchLab/ParaPower>".



# EM-Aware Reliability Optimization



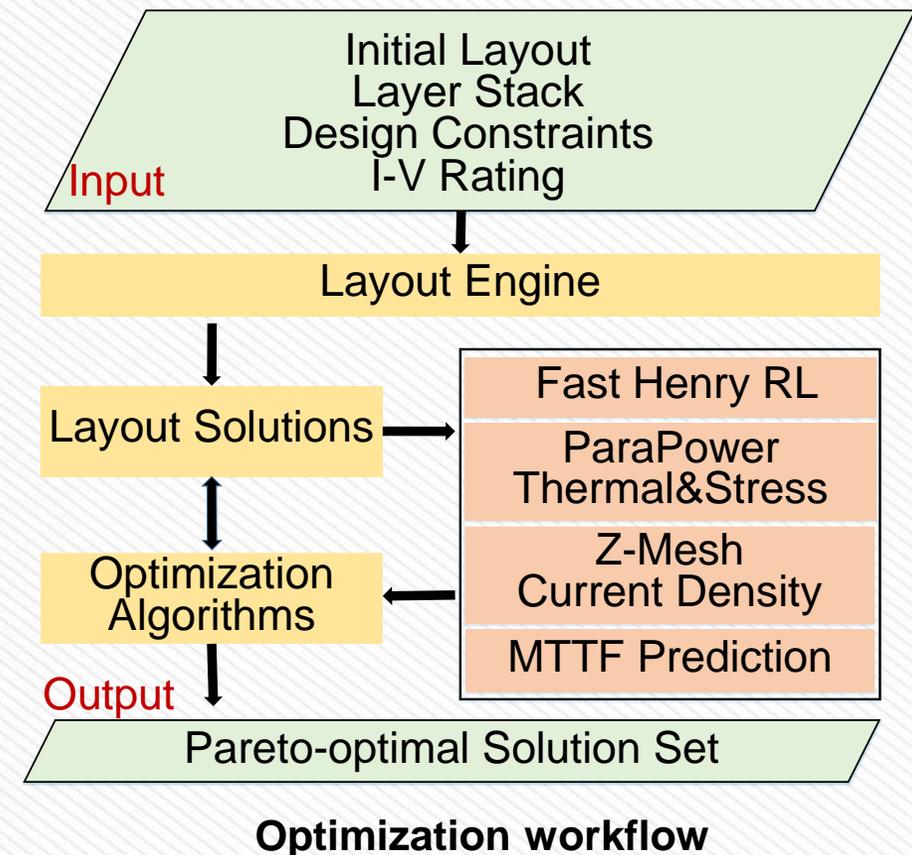
## Objectives:

- Quick assessment of risks associated with electro migration (EM) and mechanical failure of interconnects.
- Optimize power module layout to reduce the risk of failure of interconnect.

## Methodology

### Features to be considered:

- Layout generation capability with different interconnects
- Fast and accurate model for current density estimation through interconnects.
- Fast and accurate model for temperature and stress distribution



## ❑ Implementation using PowerSynth 2 APIs:



## ❑ Mean Time To Failure (MTTF) Calculation :

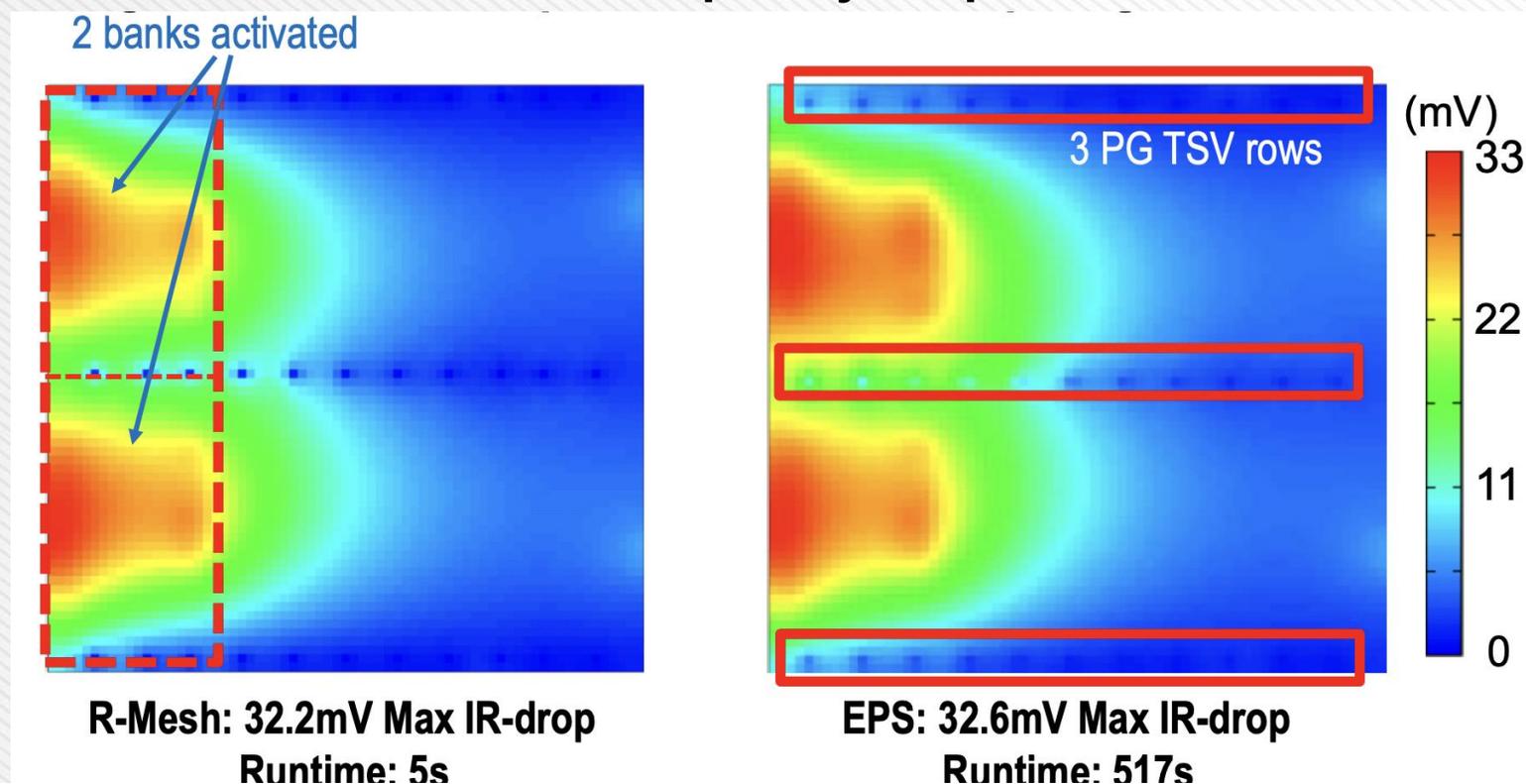
- Closed-formula approach (Black's Equation for Electromigration)

$$MTTF = \frac{A}{j^2} e^{\frac{E_a}{kT}}$$

- where, A = constant, j = current density,  $E_a$  = Activation energy, T = Temperature
- **Data-Driven Model**
  - Look-up table from experimental results
  - Parameter tuning on analytical models from experimental results

# Zmesh Current Density Model

- ❑ **Zmesh model is derived based on a fast-and-accurate resistive mesh network modeling Rmesh tool, first developed to model IR-drop in 3D DRAM**
  - Validated against Cadence EPS with 103x runtime speed up using a DDR3 layout
  - Extended to cover both DC and AC frequency for power electronics useage

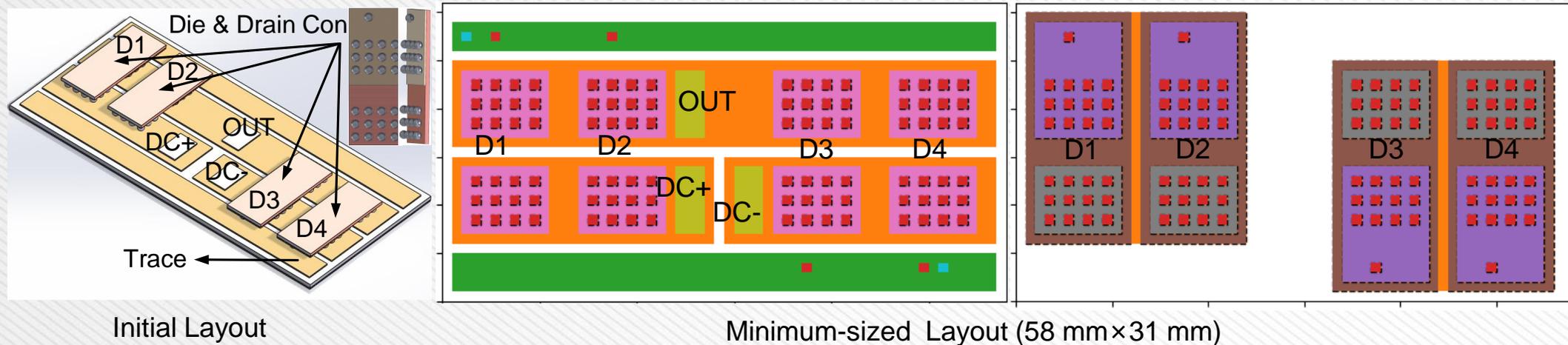


[1] Yarui Peng et al., "Design, Packaging, and Architectural Policy Co-Optimization for DC Power Integrity in 3D DRAM", in Proc. Design Automation Conference, pp. 1–6, Jun 2015.

## Layout Solution Generation

### ● Flip-Chip Design:

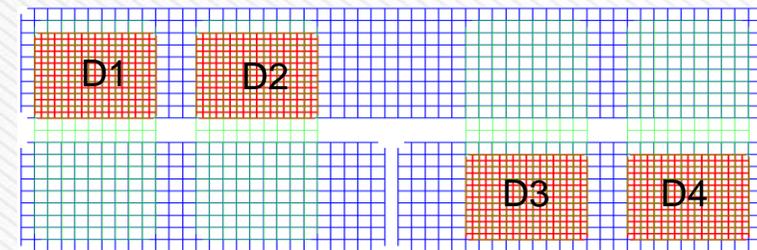
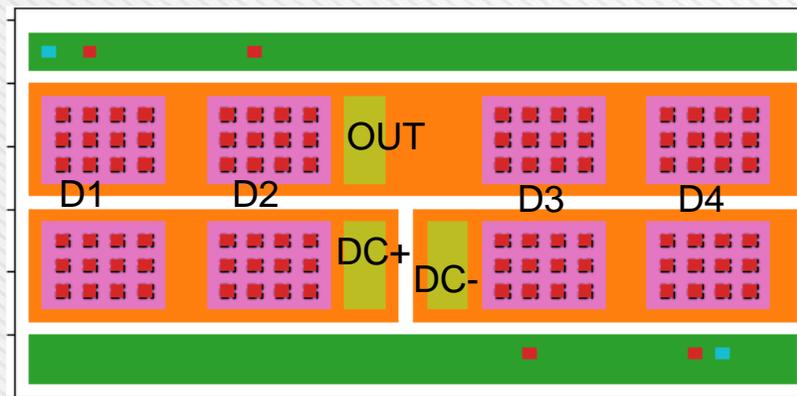
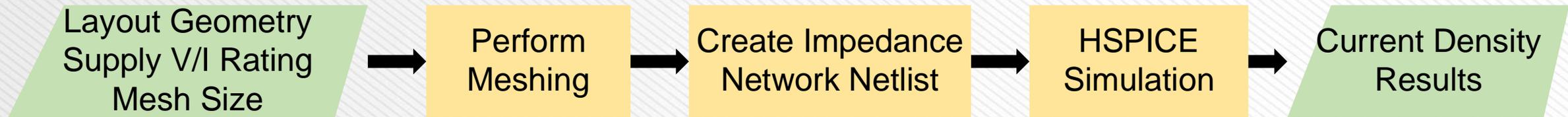
- Half-bridge module: Two SiC devices/switching position
- Source side is directly bonded
- Drain side is extended through metallic connector and bonded with solder balls.



## Current Density: Z-Mesh tool

## Temperature Distribution: ParaPower

## Workflow



Z-mesh (power loop only)

## Performance Comparison

Model	Runtime (s)	Speedup	Memory (MB)	Memory Reduction
ANSYS	310	×1	10329	×1
Z-Mesh	0.28	×1107	513	×20

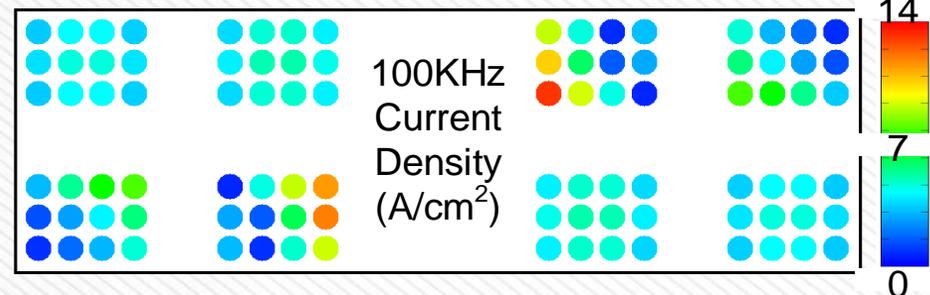
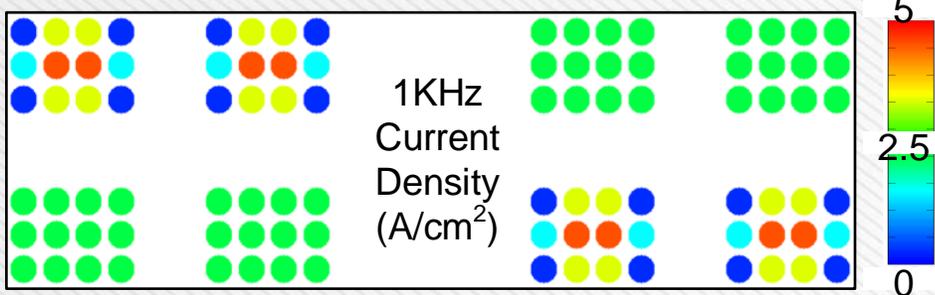
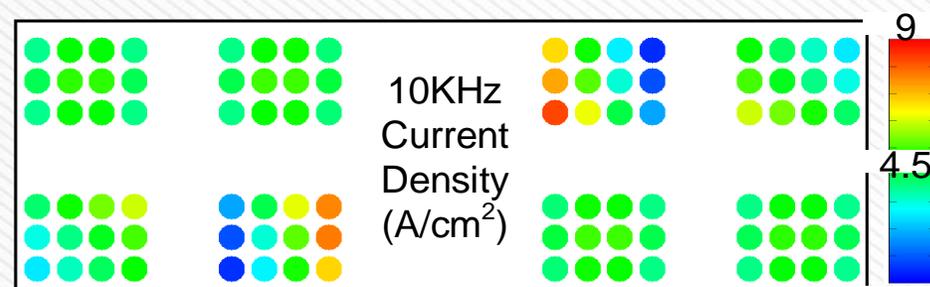
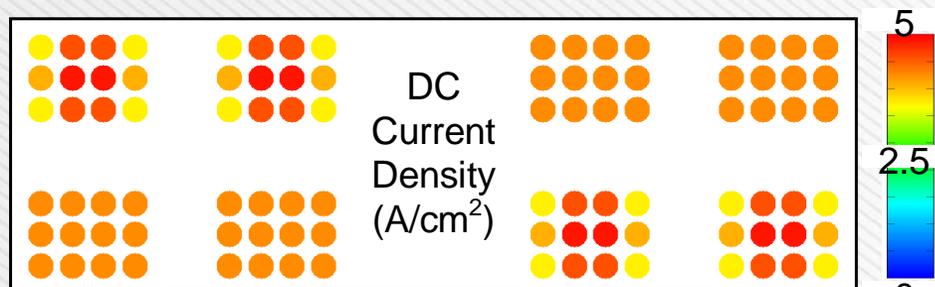


# Current Density Results



## Frequency Dependent Current Density

- At DC, intra-die current density variation is observed
- Frequency increases  $\rightarrow$  loop impedance increases  $\rightarrow$  inter-die current density variation increases
  - Solder joints close to the DC+ and DC- : Higher current density
  - Solder joints away from the DC+ and DC- : Lower current density



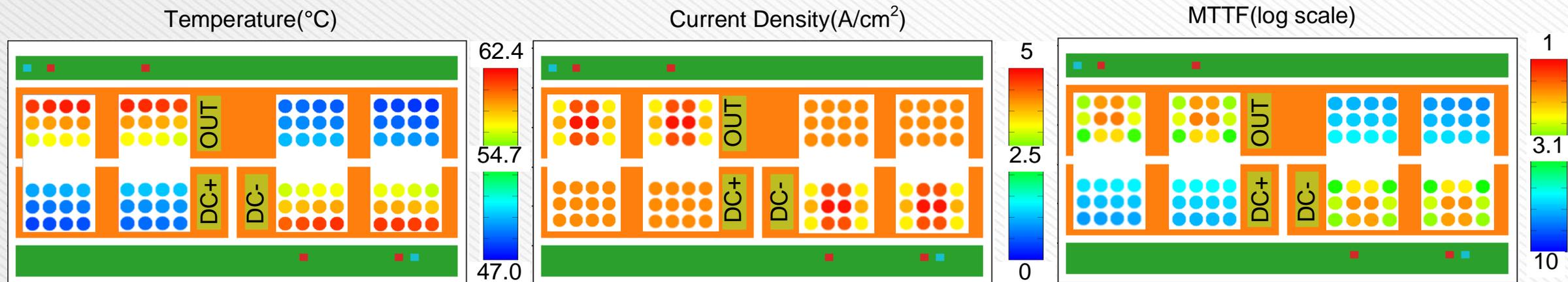


# MTTF Results



## □ MTF Evaluation: DC

- Inter-die current density negligible
- Temperature is dominant
  - Hot spots: source-side solder bumps
- MTF:
  - Lower: source-side solder bumps



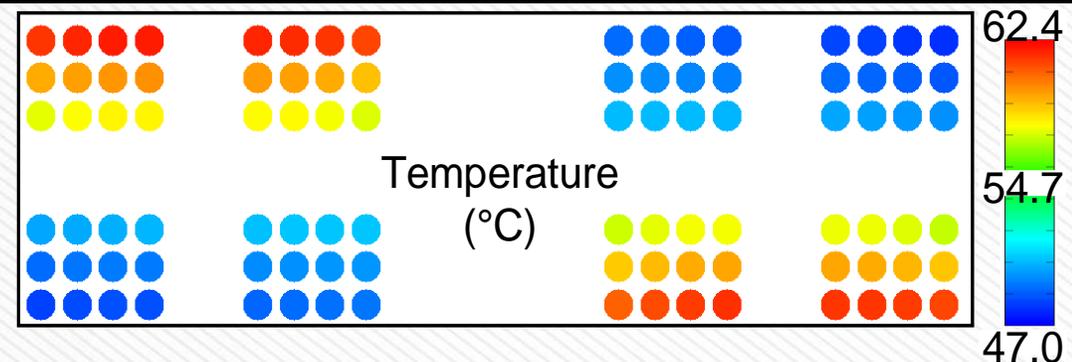


# MTTF Results

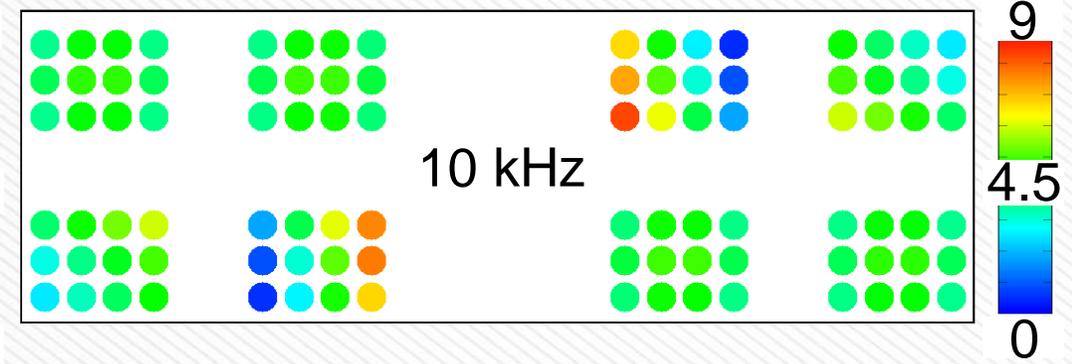
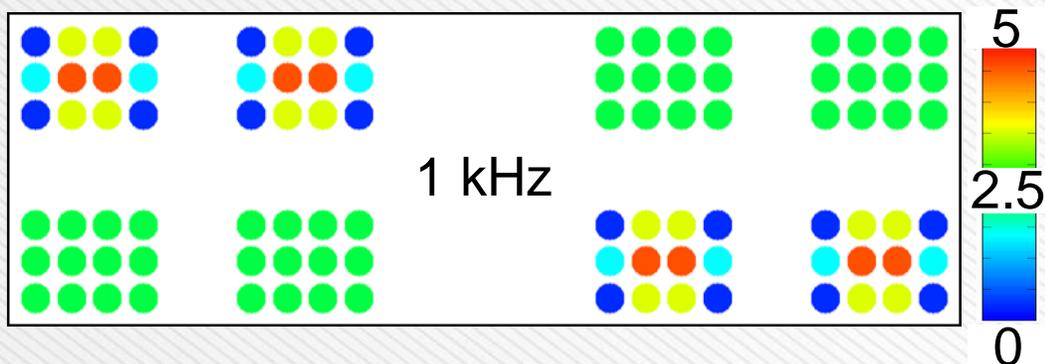


## MTTF Evaluation: AC

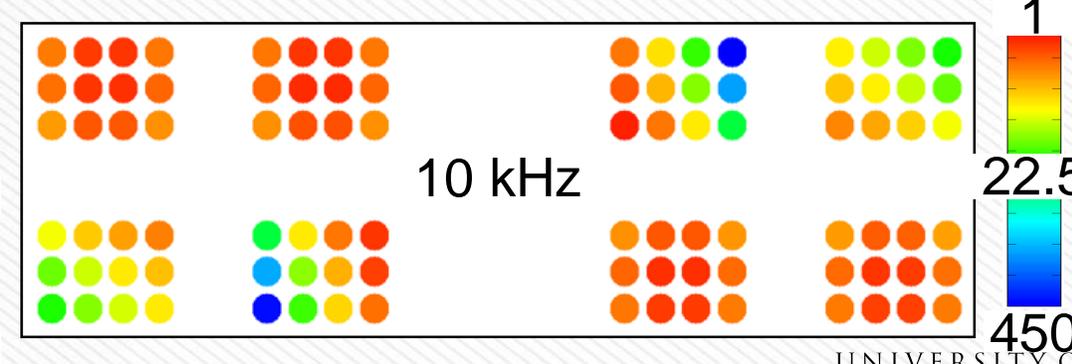
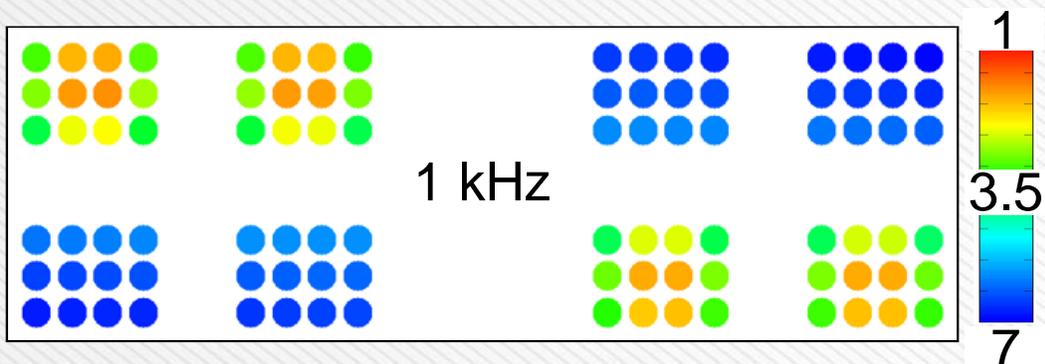
- Critical: current density and temperature
- Frequency increases → current density impact increases



Current Density (A/cm<sup>2</sup>)



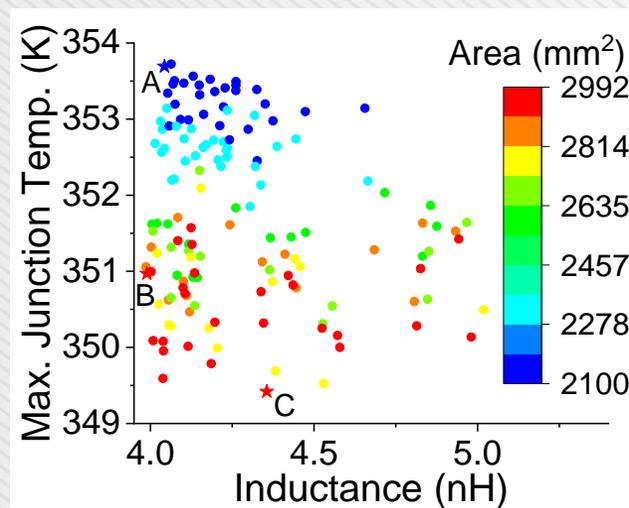
MTTF (log scale)



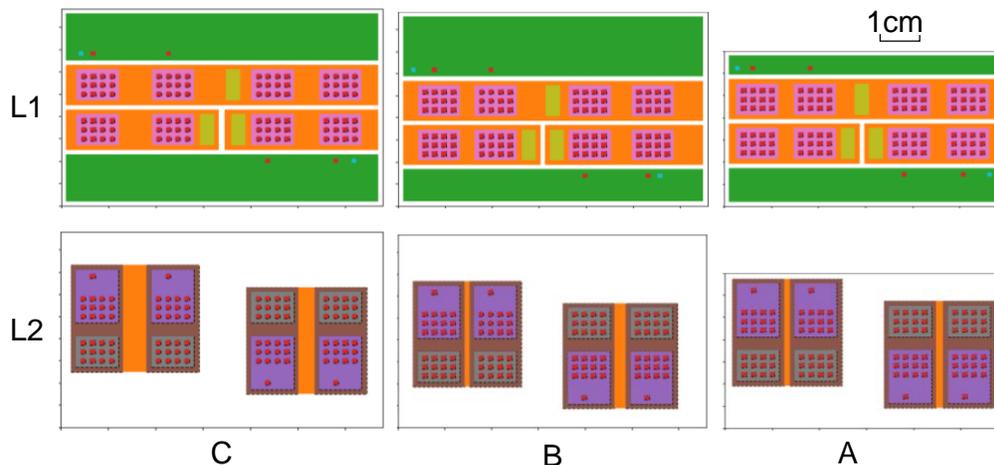
# Optimization Results

## Approach 1: Floorplan area variation

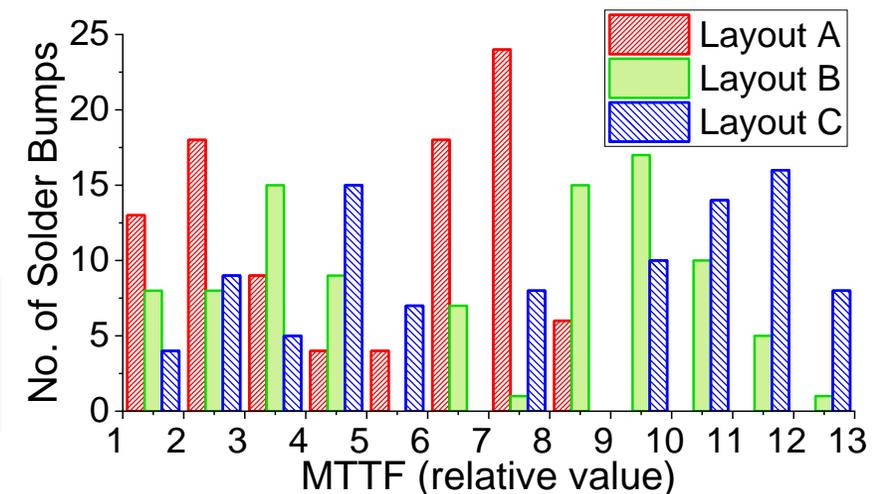
- 10 floorplan sizes : 15 solutions/size (135 s/ layout solution)
- L: FastHenry, T: ParaPower, J: Z-Mesh tool.
- MTTF evaluation at DC
  - Layout A: Highest temperature rise → lower MTTF
  - Layout C: Lowest temperature rise → Higher MTTF
  - Layout B: Balanced solution



Solution space



Three layouts

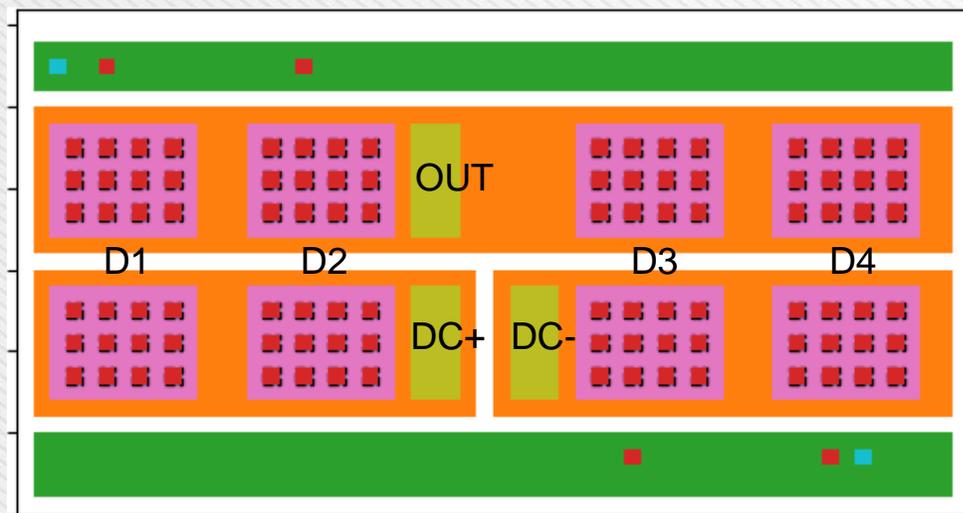


MTTF distribution of three layouts

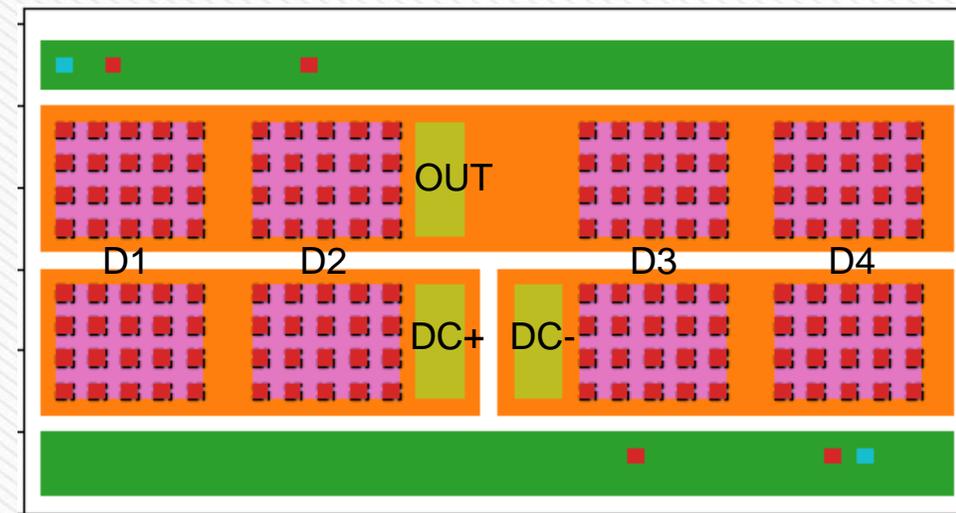
# Optimization Results

## □ Approach 2: Fixed floorplan # of solder ball variation

- Minimum-sized solution: 58 mm × 31 mm
- Larger array size → more even current distribution → less density



Case 1: 4 × 3 Array



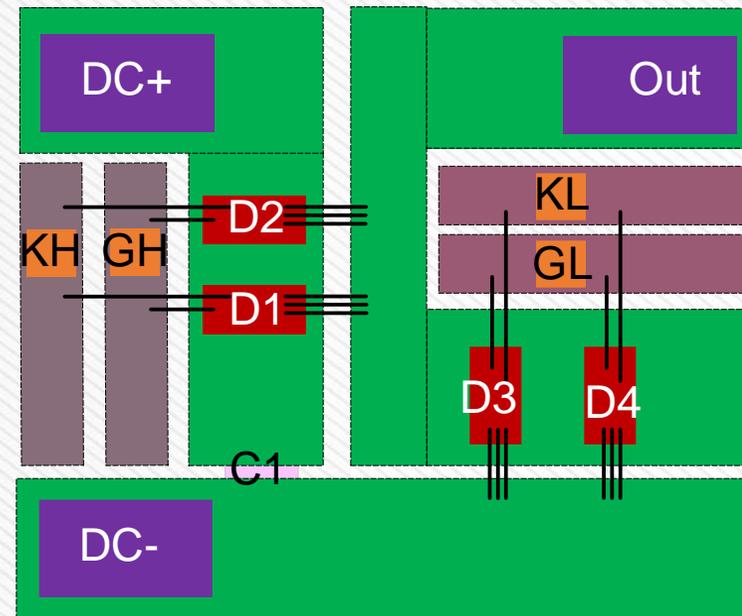
Case 2: 5 × 4 Array

Case	Solder Array	Max J (A/cm <sup>2</sup> )	Max Temp. (°C)	MTTF	Improvement
1	4 × 3	4.86	62.43	1.19	×1
2	5 × 4	3.13	62.34	2.89	×2.4

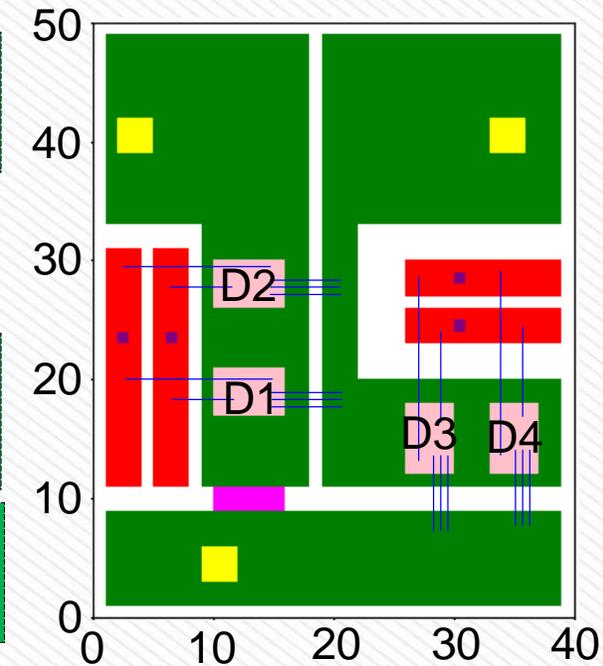
## Layout Solution Generation

### Wire-bonded 2D module:

- Half-bridge module: Two SiC devices/switching position
- Three 5-mil Al wirebonds/device
- Embedded decoupling capacitor (C)
- Hardware validated parasitic extraction result
- Temperature distribution result from ParaPower

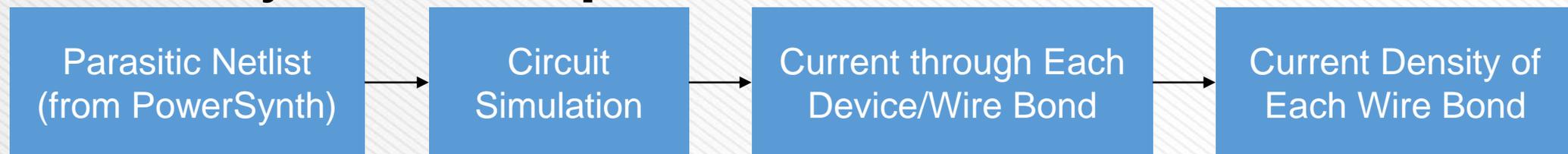


Initial Layout



Optimized Solution (40 mm × 50 mm) [1]

### Current density extraction steps:



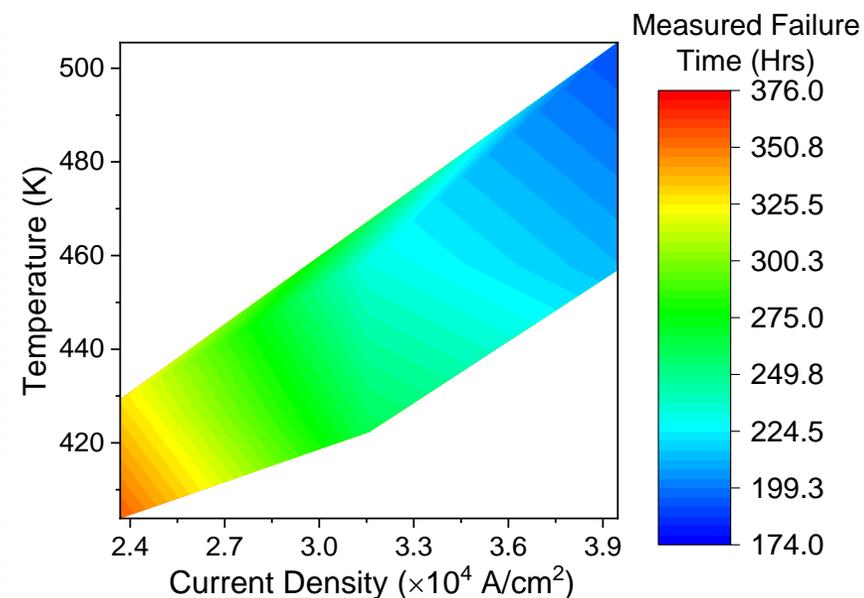
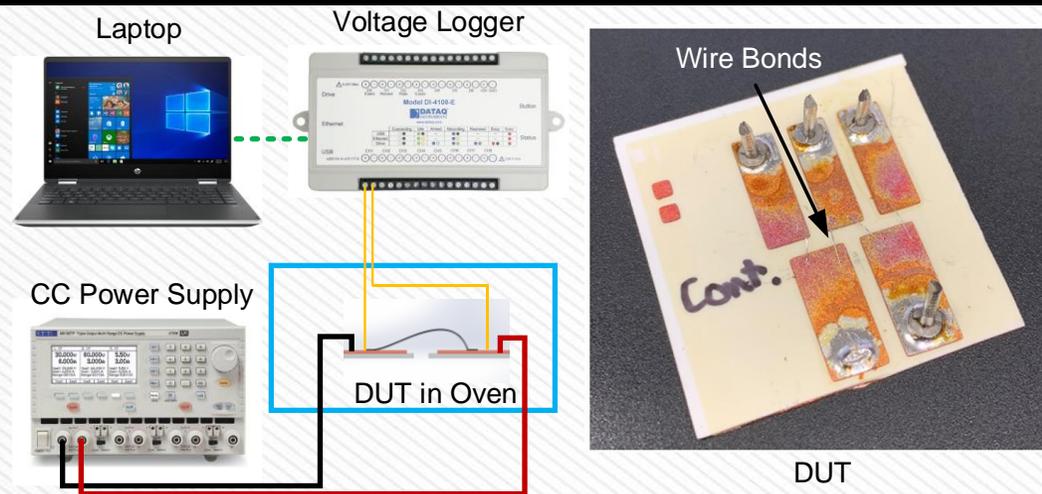
[1] Imam Al Razi et. al., "PowerSynth Design Automation Flow for Hierarchical and Heterogeneous 2.5D Multi-Chip Power Modules", IEEE Transactions on Power Electronics, vol. 36, no. 8, pp. 8919–8933, 2021.

## Wire Bonds EM Failure Experimental Setup

- Two DBC with four 5-mil Al wirebonds
- Accelerated test setup
  - Elevated ambient temperature using oven
  - Variable current densities
  - DATAQ voltage module
    - Resistance (R) change monitoring
  - Failure criteria: 10% increase in R

## Results

- Contour plot to represent aggregation of
  - the current density through the wire bonds,
  - the temperature of the wire bonds at that current density,
  - the corresponding failure time (color bar)



## ❑ Wire-bonded Module

- **Current Density Extraction**

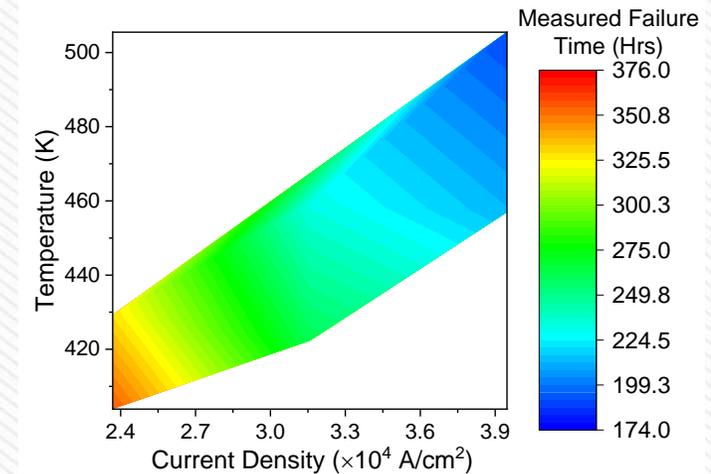
- Supply current ~ 23 A

- **Temperature**

- Measurement data from [1]

- **Reliability Metric:**

- 10% increase in R of the wire bond (from contour plot based on the experimental data)



Device	Current (A)	Temperature (K)	Wire Bond Current Density (A/cm <sup>2</sup> )	EM Failure Time (Hr)
D1	11.53	416.8	$3.03 \times 10^4$	217.4
D2	11.26	416.5	$2.95 \times 10^4$	229.6
D3	11.55	427.0	$3.03 \times 10^4$	210.8
D4	11.24	427.7	$2.95 \times 10^4$	221.9

[1] Imam Al Razi et. al., "PowerSynth Design Automation Flow for Hierarchical and Heterogeneous 2.5D Multi-Chip Power Modules", IEEE Transactions on Power Electronics, vol. 36, no. 8, pp. 8919–8933, 2021.



# Conclusions and Future Work



## □ **Conclusions:**

- **EM needs to be considered with multi-physics models and detailed layout**
- **Integrated fast and accurate models in PowerSynth2 for**
  - Current density distribution
  - Temperature distribution
  - EM-aware MTTF estimation
- **Both closed-form models and data-driven models are highly accurate with significant runtime improvement over FEM.**
- **Our EM-aware design automation flow can optimize both flip-chip and wire-bonded MCPM layouts with high accuracy and efficiency**

## □ **Future Work:**

- **More accurate current and temperature distribution across the wire bonds**
- **Incorporating stress impact in the electromigration risk assessment model**
- **Validate the optimization results through experiments**